

## Thermal Evaporator

**Purposes:** To perform thin film deposition of Al by thermal evaporation

**Process Capabilities:**

- **Wafer size:** 2 Inch at a time 2-3 wafers can be processed if required
- **Number of current sources to heat the filament:** two
- **Number of filaments that can be fitted in the system:** two
- **Material:** Al
- **Base pressure:**  $8 \times 10^{-5}$  mbar
- **Substrate temperature:** Room temperature
- **Coolant required:** Liquid Nitrogen
- **Additional facility:** Shadow masks of 1mm diameter available for making MOS capacitors.

